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(30) Priority Data: 08/568,910 7 December 1995 US (07.12.95)	(54) Title: TACKIFIERS AND A PROCESS TO OBTAIN TACKIFIERS	
(71) Applicant: EXXON CHEMICAL PATENTS INC. [US/US]; 5200 Bayway Drive, Baytown, TX 77520-5200 (US).	(57) Abstract Resins which are the copolymers an alpha-olefin, a cyclic olefin, and an aromatic-group-containing monomer are provided. The cyclic olefins retain their cyclic structures and the aromatic-group-containing monomers retain their aromatic structures after copolymerization into the resin product. Methods for production of the new resins in the presence of a metallocene catalyst system are also provided. New adhesive compositions containing the resin and articles using the new adhesive compositions are also part of the invention.	
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(30) Priority Data: 08/568,916 7 December 1995 US (07.12.95)	(54) Title: ISOLATION OF NOVOLAK RESIN WITHOUT HIGH TEMPERATURE DISTILLATION AND PHOTORESIST COMPOSITION THEREFROM	
(71) Applicant: HOECHST CELANESE CORPORATION [US/US]; Route 202-206 North, Somerville, NJ 08876 (US).	(57) Abstract The present invention provides a method for producing a water insoluble, aqueous alkali soluble novolak resins having consistent molecular weight and superior performance in photoresist composition, by isolating such novolak resin without high temperature distillation. A method is also provided for producing photoresist composition from such a novolak resin and for producing semiconductor devices using such a photoresist composition.	
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